

FAST RECOVERY DIODES

■ Junction Size: Square 180 mils

■ Wafer Size:

1000 and 1200 V ■ V_{RRM} Class: Passivation Process: **Glassivated MOAT**

■ Reference IR Packaged Part: 20ETF Series

Major Ratings and Characteristics

	Parai	neters	Units	Test Conditions	
ľ	$V_{\rm FM}$	Maximum Forward Voltage	1350mV	$T_J = 25$ °C, $I_F = 20$ A	
	V_{RRM}	Reverse Breakdown Voltage Range	1000and1200V	$T_J = 25^{\circ}C, I_{RRM} = 100 \mu\text{A}$ (1))

⁽¹⁾ Nitrogen flow on die edge.

Mechanical Characteristics

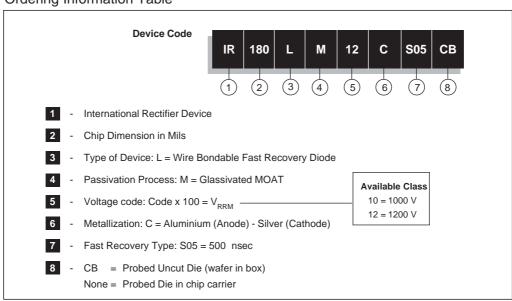
Nominal Back Metal Composition, Thickness	Cr-Ni-Ag (1 KA-4 KA-6 KA)
Nominal Front Metal Composition, Thickness	100% AI, (20 µm)
Chip Dimensions	180 x 180 mils (4.57x4.57 mm) - see drawing
WaferDiameter	100 mm, with std. < 110 > flat
WaferThickness	260 μm
Maximum Width of Sawing Line	45 µm
Reject Ink Dot Size	0.25 mm diameter minimum
InkDotLocation	Seedrawing
Recommended Storage Environment	Storage in original container, in dessicated nitrogen, with no contamination

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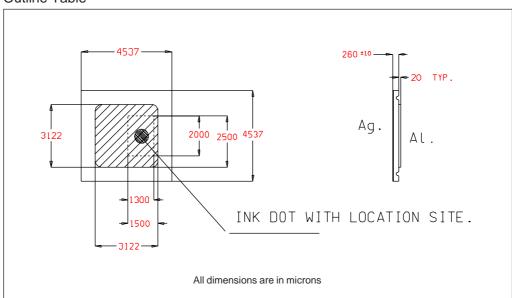
IR180LM..CS05CB Series

Bulletin I0125J 07/97

Ordering Information Table



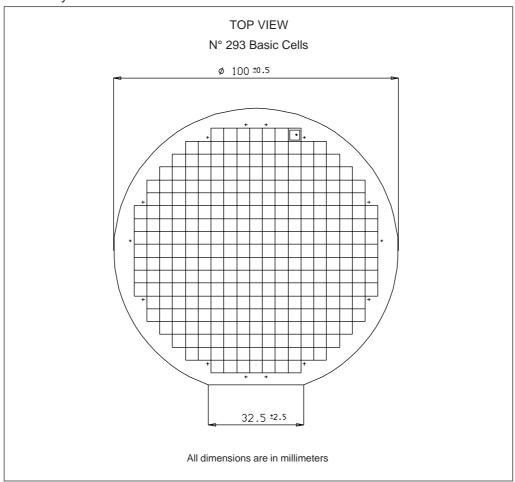
Outline Table



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Wafer Layout



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